

REMARKS

Reconsideration and withdrawal of the rejections set forth in the above-mentioned Office Action in view of the foregoing amendments and the following remarks are respectfully requested.

Claims 1-10 are now pending in this application, with Claim 1 being the sole independent claim. Claims 1-9 have been amended and Claim 10 is newly-presented herein.

Claims 1-6 and 9 were rejected under 35 U.S.C. § 103(a) as allegedly being unpatentable over EP 1 380 423 (Kubota et al. '423) in view of JP 2001-179990 (Imamura). Claims 1-9 were rejected under 35 U.S.C. § 103(a) as allegedly being unpatentable over EP 1 380 425 (Kubota et al. '425) in view of Imamura. Claim 9 was rejected under 35 U.S.C. § 102(b) as allegedly being anticipated by or, in the alternative, under 35 U.S.C. § 103(a) as allegedly being unpatentable over Imamura. These rejections are respectfully traversed.

Kubota et al. '423 relates to a method for producing a fine structured member and a fine hollow structure, useful for producing a liquid discharge head. The Examiner considers Kubota et al. '423 to include the steps of forming a mold pattern with a removable resin in a portion where a liquid flow path is to be formed on a substrate having a liquid discharge energy generating element, coating and hardening a covering resin layer on the substrate so as to cover the mold pattern, and removing, by dissolution, the mold pattern, thereby forming a liquid flow path having a hollow structure. However, the Examiner notes that Kubota et al. '423 is deficient at least with respect to an inhibitor of cationic polymerization in the covering resin layer.

The Examiner also cites Kubota et al., '425 for teaching a process of forming a first positive photoresist layer on a substrate including an ink discharge pressure generating element, coating a second positive resist layer, patterning the second resist layer to form a second flow path pattern, patterning the first positive resist layer to form a first flow path pattern, coating a photosensitive resin composition to form a liquid flow path forming material, patterning an ink discharge port in the liquid flow path forming material, and removing the flow path patterns. However, the Examiner notes that Kubota et al., '425 is also deficient at least with respect to providing the liquid flow path forming material with an inhibitor of cationic polymerization.

Thus, Kubota et al., '423 and Kubota et al., '425 fail to disclose or suggest important features of the present invention recited in independent Claim 1.

In order to overcome the deficiencies of Kubota et al., '423 and Kubota et al., '425, the Examiner relies on the teachings of Imamura. Imamura relates to a method for manufacturing a liquid ejection recording head that includes coating a substrate provided with ejection pressure generating elements and a solid layer occupying at least a part serving as a channel with a nozzle forming member. Applicants submit that in Imamura, while a solid layer or liquid material coated thereon may include a cationic photopolymerization inhibitor, that layer or liquid material does not undergo the lithographic process and is not a member where a discharge port is formed. Note Applicants's specification at page 2, lines 13-17.

Applicants submit, therefore, that Imamura fails to overcome the deficiencies of Kubota et al., '423 and Kubota et al., '425 noted above with respect to Claim 1.

Thus, independent Claim 1 is patentable over the citations of record.

Reconsideration and withdrawal of the §§ 102 and 103 rejections are requested.

For the foregoing reasons, Applicants respectfully submit that the present invention is patentably defined by independent Claim 1. Dependent Claims 2-10 are also allowable, in their own right, for defining features of the present invention in addition to those recited in their respective independent claims. Individual consideration of the dependent claims is requested.

Applicants submit that the present application is in condition for allowance. Favorable reconsideration, withdrawal of the rejections set forth in the above-noted Office Action, and an early Notice of Allowability are requested.

Applicants' undersigned attorney may be reached in our Washington, D.C. office by telephone at (202) 530-1010. All correspondence should continue to be directed to our below-listed address.

Respectfully submitted,

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